

20th Anniversary of KSDT
KISM 2022
Korean International Semiconductor Conference on Manufacturing Technology 2022
November 13-16, 2022 | Paradise Hotel Busan (Haeundae Beach), Busan, Korea

Session Title:	[TD3] EUV Mask, Pellicle, Inspection II
Session Date:	November 15 (Tue.), 2022
Session Time:	14:30-16:15
Session Room:	Room D (Sidney Room, 2F)
Session Chair:	Dr. Donggun Lee (ESOL, Inc., Korea)

[TD3-1] [Plenary] 14:30-15:15

0.33 NA EUV Systems for High-Volume Manufacturing

Roderik van Es (ASML, Netherlands)

[TD3-2] 15:15-15:35

Performance Verification and Development Status of EUV Pellicle for High Power

Cheol Shin, Buoung Hoon Seung, Chang Hun Lee, Juhee Hong, Min Wook Jung, Chulkyun Park, Byeong Sung Yu, Munsu Choi, Donghoi Kim, and Kwan Hui Jung (S&S Tech Corp., Korea)

[TD3-3] 15:35-15:55

Metrology and Inspection Technology for the High-NA EUV Lithography

Sangsul Lee (POSTECH, Korea)

[TD3-4] 15:55-16:15

Advanced EUV Mask with Platinum-Tungsten Alloy for High-NA EUV Lithography

Yunsoo Kim, Dongmin Jeong, Minsun Cho, and Jinho Ahn (Hanyang Univ., Korea)